AMENDMENTS TO THE CLAIMS

The following listing of claims will replace all prior versions, and listings, of claims in the application:

Listing of Claims:

1. (Currently Amended) A device for treating a web material in a plasma enhanced chemical vapor deposition process, the device comprising:

a vacuum chamber (1) ~~with means (2)~~equipped for maintaining a constant reduced pressure therein ~~within the chamber (1)~~ and,

arranged within the vacuum chamber (1) are,

~~a web supporting and transporting means, a magnetron means facing the web (4) supported and transported by the supporting and transporting means and a gas supply means for supplying a process gas or process gas mixture to a space (10) between the supporting and transporting means and the magnetron means, wherein the magnetron means comprises~~ a rotating drum for supporting and transporting a web material lying against a circumferential surface of the drum, the drum being one of electrically grounded, electrically floating, and negatively biased,

a plurality of independent magnetron electrodes (6) ~~with~~comprising rectangular magnetron faces with a length and a width, each magnetron electrode (6) being powered with an alternating voltage by its own power supply ~~means~~unit (7), and

~~the magnetron faces being arranged beside each other in parallel and at a distance from the supporting and transporting means, and wherein the supporting and transporting means is one of electrically grounded, electrically floating, and negatively biased~~

a plurality of gas supply lines,

wherein the magnetron electrodes are arranged with the magnetron faces facing the circumferential surface of the drum and at a same distance therefrom, the lengths of the magnetron faces extending parallel to a drum axis and the widths of the magnetron faces extending substantially tangential to the circumferential surface, and

wherein the gas supply lines extend between neighboring magnetron faces or within the magnetron faces and substantially parallel to the drum axis.

2. (Cancelled)

3. (Currently Amended) The device according to claim 1, wherein the ~~gas supply means comprises~~ gas supply lines (8, 8') ~~extending~~extend between adjacent magnetron faces.

4. (Cancelled)

5. (Previously Presented) The device according to claim 3, wherein the supply lines (8, 8') comprise rows of gas outlets arranged for gas injection either substantially perpendicular or substantially parallel to the magnetron faces.

6. (Currently Amended) The device according to claim 41, further comprising wall elements (20) extending along the longitudinal edges of the magnetron faces and towards the ~~supporting and transporting means~~rotating drum.

7. (Currently Amended) The device according to claim 41, wherein the magnetron electrode (6) constitutes a twin magnetron.

8. (Currently Amended) The device according to claim 1, wherein ~~gas~~ gas from said plurality of gas supply lines is supplied to the space (10) between magnetron faces and the ~~supporting and transporting means~~rotating drum is allowed to be removed in an axial direction and/or between adjacent magnetron faces.

9. (Previously Presented) The device according to claim 1, wherein the magnetron faces comprise electrode pieces (34) of a non magnetic material extending over the magnetic poles constituting the magnetron face.

10. (Currently Amended) The device according to claim 9, wherein the electrode pieces (34) of the magnetron faces comprise channels (35) ~~that are connected to a means for circulating a cooling medium through the channels (35)~~ for receiving a cooling medium.

11. (Previously Presented) The device according to claim 1, wherein the magnetron electrodes (6) constitute magnetrons of an unbalanced type.

12. (Previously Presented) The device according to claim 11, wherein the magnetron faces comprise permanent magnetic central and peripheral poles (30 and 31), the central pole (30) having a magnetic strength that is about half of a magnetic strength of the peripheral pole (31).